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PN - JP60024016 A 19850206  
TI - MANUFACTURE OF PHOTOETCHING MASK  
AB - PURPOSE: To facilitate the formation of a photoetching mask for a conical or spherical surface by a method wherein a metallic model, to which prescribed recessed parts are provided, is produced and a transparent resin or glass layer, to be used as a die, is formed on the surface of the model.  
- CONSTITUTION: A metallic model 1, to which recessed parts of prescribed groove, pattern, shape and the like are provided, is produced. As the case may be, a finished product itself may be used as a model. Then a die 2 which covers the model 1 is made. After the model 1 is covered with the die 2, transparent resin 3 or glass is poured into a space formed by the model 1 and the die 2 and hardened. Then the die 2 and the model 1 are removed to obtain a mold 41. Then opaque resin 5 or opaque glass is poured into grooves 42 of the mold 41 and hardened to obtain a mask 4. With this constitution, not only when the surface of an object to be processed is a flat plane but also when it is a conical or spherical surface, a photoetching mask can be produced easily.  
I - H01L21/30 ; G03F1/00  
PA - NIPPON SEIKO KK  
IN - NAKAJIMA SHIGERU; others: 02  
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